

| L Number | Hits | Search Text  | DB  | Time stamp       |
|----------|------|--|---|------------------|
| 1        | 0    | (emitter) with (photo photomask photoresist mask photolayer resist pattern patterning masking masked) with (angle) and ((438/20,317,342,343,344,345,346,338,for.471,for.472).CCLS) and @pd>=20030517         | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/05 12:06 |
| 2        | 0    | (emitter) with (photo photomask photoresist mask photolayer resist pattern patterning masking masked) with (acute oblique) and ((438/20,317,342,343,344,345,346,338,for.471,for.472).CCLS) and @pd>=20030517 | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/12/05 12:06 |